

INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)				Attorney Docket No.: 46884-5429		Serial No.: 10/551,195	
PTO Form 1449				Applicants: Seiichi NAGATA		Page 1 of 1	
				Filing Date: September 29, 2005		Group Art Unit: Unassigned	
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Sub Class	Filing Date
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Sub Class	Translation YES NO
	/JL/	10-133047	May 22, 1998	JP			Abstract
	/JL/	11-242125	Sept. 7, 1999	JP			Abstract
	/JL/	2000-047045	Feb. 18, 2000	JP			Abstract
	/JL/	11-014848	Jan. 22, 1999	JP			Abstract
	/JL/	10-160950	Jun. 19, 1998	JP			Abstract
	/JL/	10-133048	May 22, 1998	JP			Abstract
	/JL/	10-300963	Nov. 13, 1988	JP			Abstract
	/JL/	61-180449	Aug. 13, 1986	JP			Abstract
	/JL/	52-063685	May 26, 1977	JP			Abstract
	/JL/	09-292540	Nov. 11, 1997	JP			Abstract
OTHER DOCUMENTS							
(Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.)							
	/JL/	M.E. Lines, "Can The Minimum Attenuation of Fused Silica Be Significantly Reduced By Small Compositional Variations? I. Alkali Metal Dopants"; Journal of Non-Crystalline Solids 171, 1994, pp. 209-218					
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	/JL/	V.P. BONDARENKO et al., "Optical Waveguide Based On Oxidized Porous Silicon", Microelectronic Engineering 28, 1995, pp. 447-450					
Examiner	/Jonathan Langman/				Date Considered 12/30/2008		
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